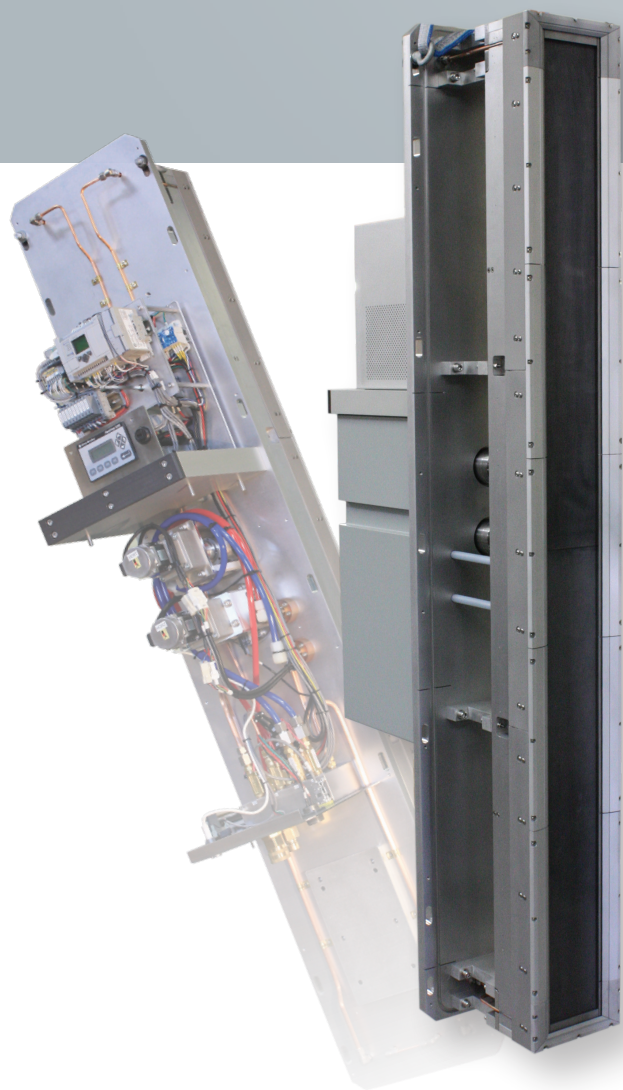


GPi



MMPM™ **MOVING MAGNET** **PLANAR MAGNETRON**

Innovative Solution to Poor Target Utilization

- **60% Target Utilization Guaranteed***
- **Excellent Deposition Film Properties**
- **Compact, Easily Retrofittable Design**
- **Extended Production Runs**
- **Scalable Design**

* Patent Pending



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The MMPM™ Advantage

MOVING MAGNET TECHNOLOGY

Localized target wear is eliminated by bidirectional movements of the magnet assembly.

- 60% TARGET UTILIZATION
- EXCELLENT DEPOSITION UNIFORMITY
- SIMPLE, RUGGED MECHANISM
- WEAR OPTIMIZED BY SIMPLE COMPUTER SIMULATION

ADVANCED MAGNETICS:

- > 1100 GAUSS AT TARGET SURFACES
- SUPERIOR FILM QUALITY
- CONSISTENT RUN-TO-RUN FILM PROPERTIES

ECONOMIC TARGET TILES:

- SIMPLE TARGET TILE DESIGN:
 - Easy to manufacture
 - No target bonding required
- PRECIOUS METALS (COSTLY TARGET MATERIALS)
- ENABLES QUICK TARGET CHANGES



Single 125 mm tile

Single Mov-Mag™ target tile shows the erosion profile

MANY BENEFITS:

- REDUCED COST OF OWNERSHIP:
 - Decreased material costs
 - Minimized downtime
- EXTENDED PRODUCTION RUNS
 - Less frequent target replacement
- LOW MAINTENANCE
- COMPACT FORM FACTOR
 - Easy retrofits into existing tools
- SCALABLE DESIGN
- DC, PULSED DC, AC SPUTTERING OF REACTIVE INSULATORS

TYPICAL APPLICATIONS:

- CERAMIC ITO SPUTTERING
- RARE AND PRECIOUS TARGET MATERIALS



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